

**IN THE SPECIFICATION**

Please replace the paragraph beginning on page 14, line 26, and ending on page 15, line 7 with the following rewritten paragraph:

A1 --This deposit shield 50 is made of a conductive material such as aluminum, formed into a cylindrical shape having both ends opened and, as shown in FIG. 6, fixed through a spacer 53 in the vacuum processing area 43. The deposit shield 50 is grounded to have a GND potential equal to the potential of the processing chamber.

The deposit shield 50 also has a partial notch portion 57 into which portion the raised shutter 49 is fitted.--

Please replace the paragraph beginning on page 15, line 8, with the following rewritten paragraph:

A2 --Further, an electric heater (~~not shown~~) 58 is built in each of the shutter 49 and the deposit shield 50 to so as to function to prevent heat loss in the vacuum processing area 43, to improve treatment efficiency, to suppress the adhesion of a reactive product and to lengthen a maintenance cycle.--

Please replace the paragraph beginning on page 15, line 14, with the following rewritten paragraph:

A3 --This shutter 49 is coupled to one end of a driving shaft 51 airtightly introduced from the atmospheric area 44 on the lower portion of the processing chamber 41 using a magnetic fluid seal or the like. The other end of this driving shaft 51 is coupled to an air cylinder 52. The air cylinder 52 drives the shutter 49 to be vertically elevated. Namely, if the substrate is carried into and out of the processing chamber through the carrier port 47, the shutter 49 is descended to be retreated.

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When plasma is generated, the shutter 49 is raised to be fitted into the notch portion

A3  
w+

57 of the deposit shield 50 to thereby form an even curve.--

